

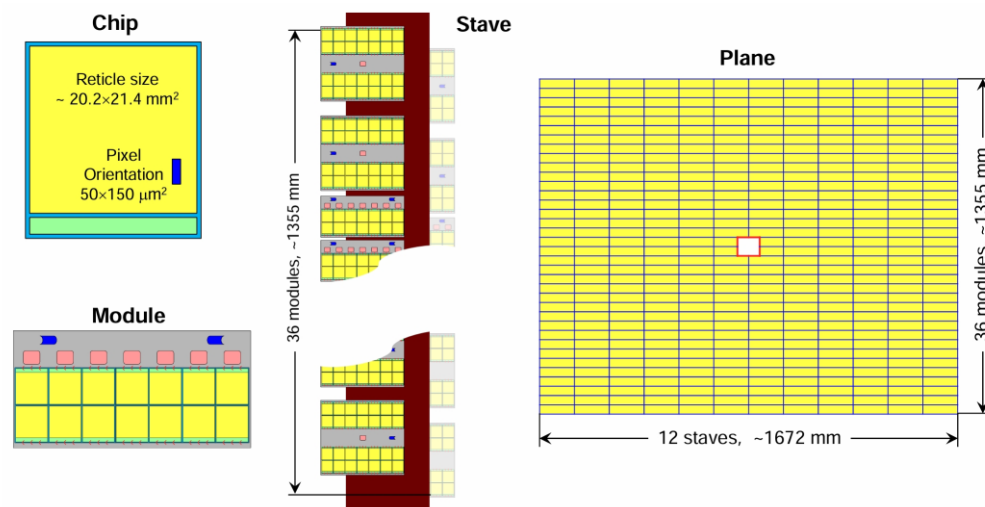
Sensor Development for LHCb Upstream Pixel Tracker

Cheng Zeng 曾程 (Institute of High Energy Physics, CAS)
On behalf of COFFEE team



CMOS SENSOR IN
FIFTY-FIVE NM PROCESS

- LHCb Upgrade II requires tracker with better radiation hardness and spatial resolution.



Upstream Pixel Tracker for LHCb Upgrade II

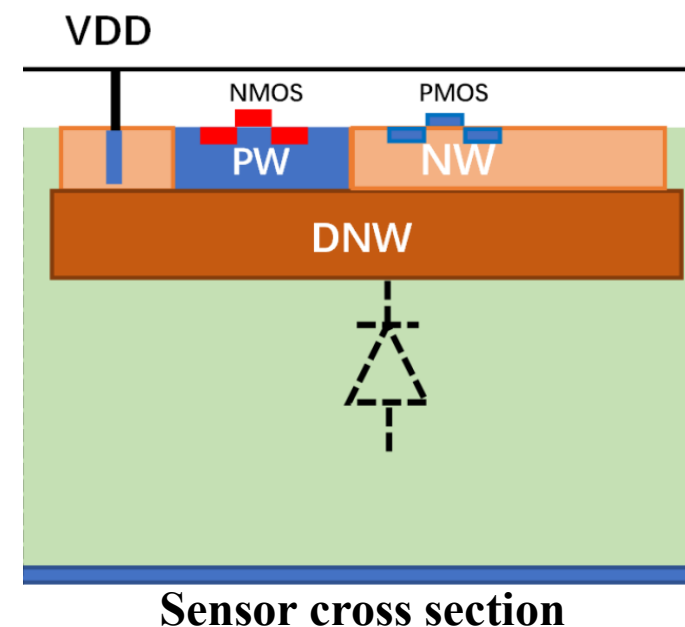
Area: $\sim 8 \text{ m}^2$

Radiation hardness: $\sim 3 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$

Time resolution: 3 – 5 ns, capability to tag 25 ns bunch crossing

Power consumption: $\sim 200 \text{ mW}/\text{cm}^2$

- HVCMOS advantages:
 - MAPS, Excellent spatial resolution, no need to bump bond the sensor and ASIC
 - Large deep n-well as charge collection node, high voltage bias; Fast charge collection, less trap effect
 - Enclose readout circuit inside deep n-well. Intrinsically radiation hardness



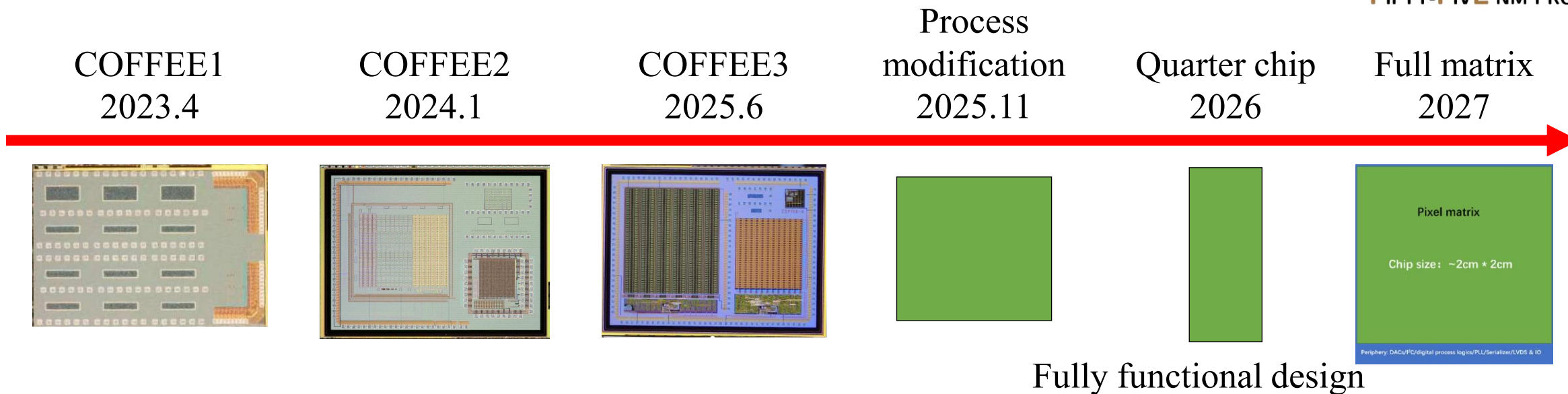
CMOS sensOr in Fifty-FivE nanometer procEss chips

- Targeting to achieve full-size, full function chips meeting the LHCb UP Tracker requirements in a few year.

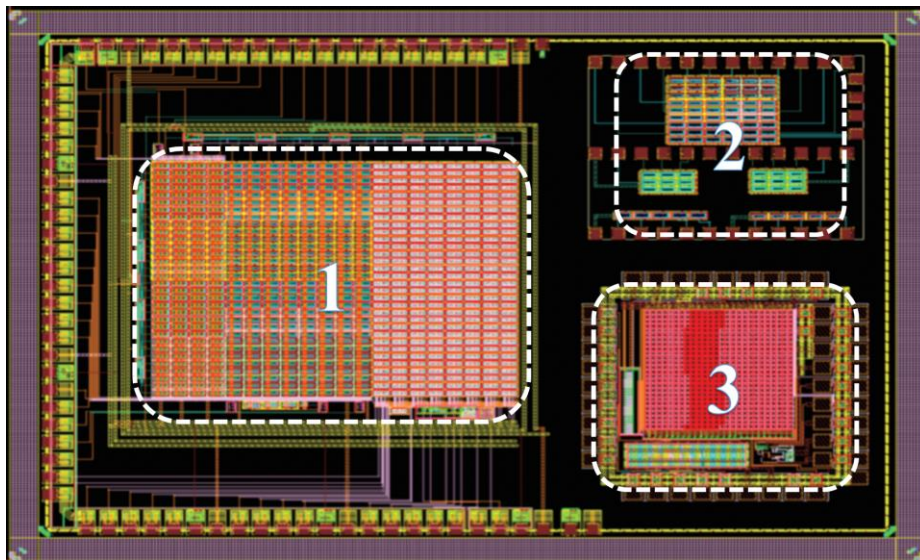
- COFFEE1: Validate the 55 nm low leakage process
- COFFEE2: Explore and validate the 55 nm HV-CMOS process
- COFFEE3: Validate the readout circuit structures and core performances



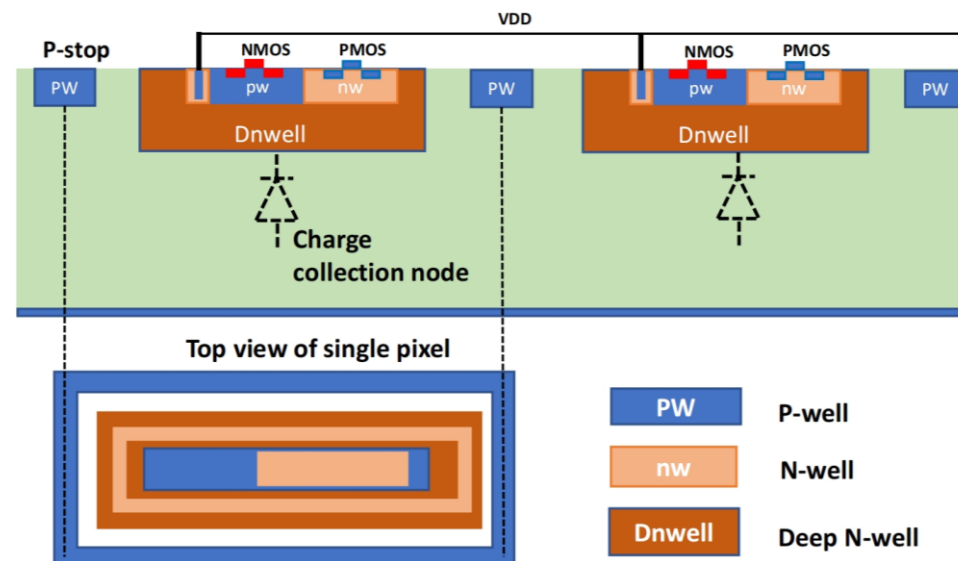
CMOS SENSOR IN
FIFTY-FIVE NM PROCESS



COFFEE2 chip, $3 \times 4 \text{ mm}^2$, the first HVCMOS chip in 55 nm process, triple-well structure

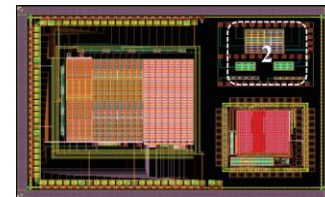


COFFEE2 chip floorplan



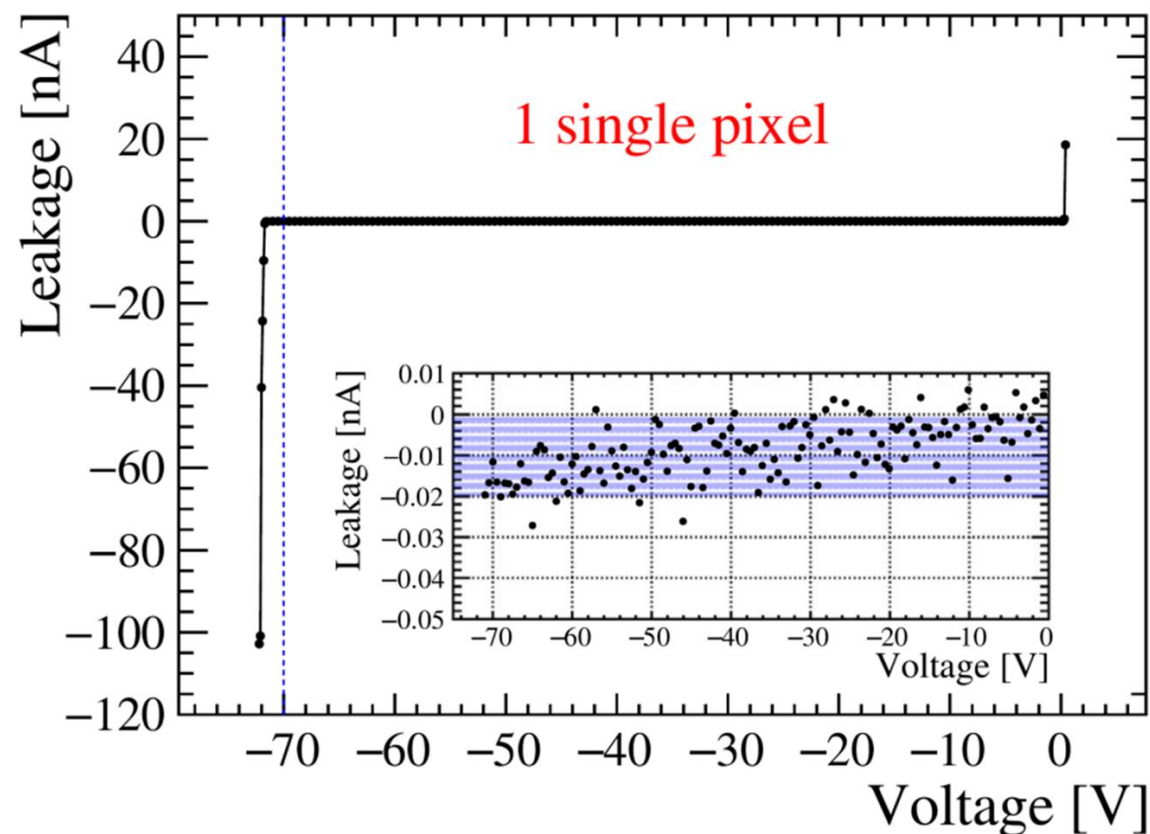
Sensor cross section

- Section 1: 32 rows $\times$ 20 columns pixels matrix, with sensor and in-pixel circuit. Studying for in-pixel charge sensitive amplifier (CSA), CMOS and NMOS comparator design for process validation. **JINST 20 (2025) C10011**
- Section 2: Passive diode, real validation of sensor.
- Section 3: 26 rows $\times$ 26 columns pixels matrix, with sensor, in-pixel circuit and digital readout periphery for novel electronics structure study. **JINST 20 (2025) C03023**

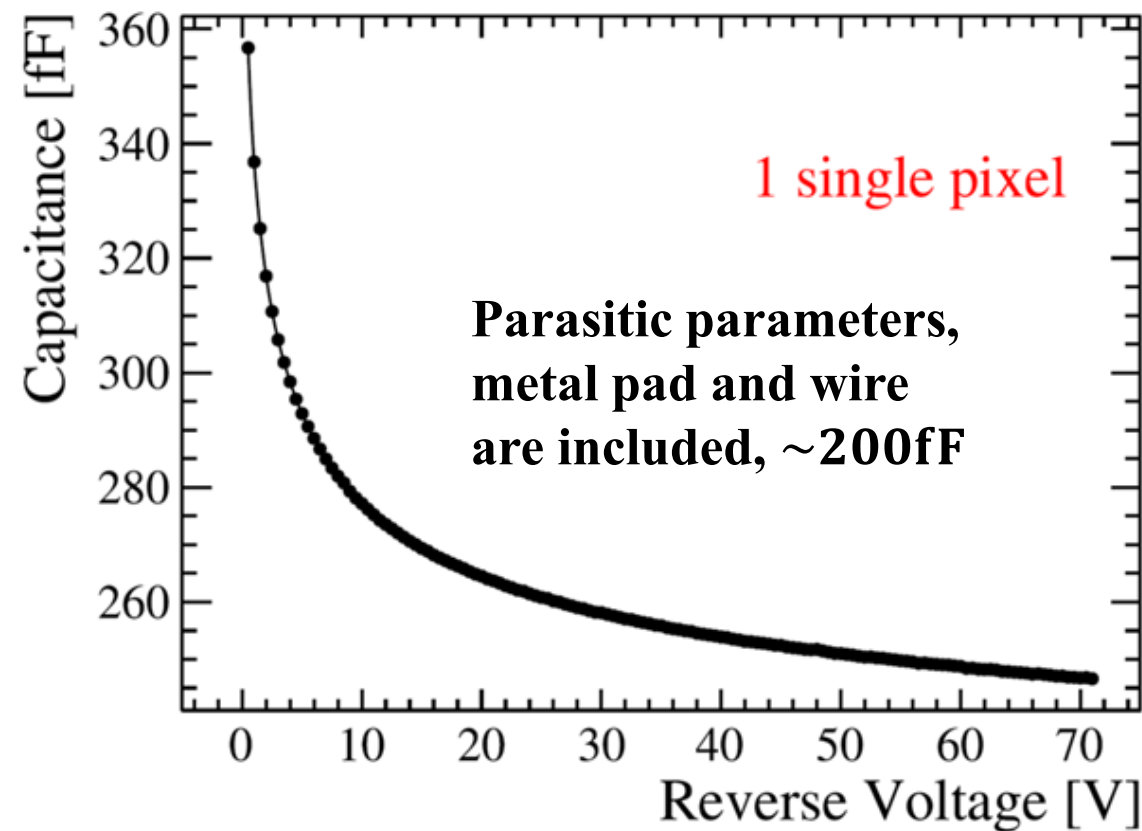


Section 2, Passive diode

- Breakdown Voltage: ~ -70 V
- Leakage: ~ 10 pA
- Capacitance: $30 \sim 40$ fF at -70 V



I-V curve

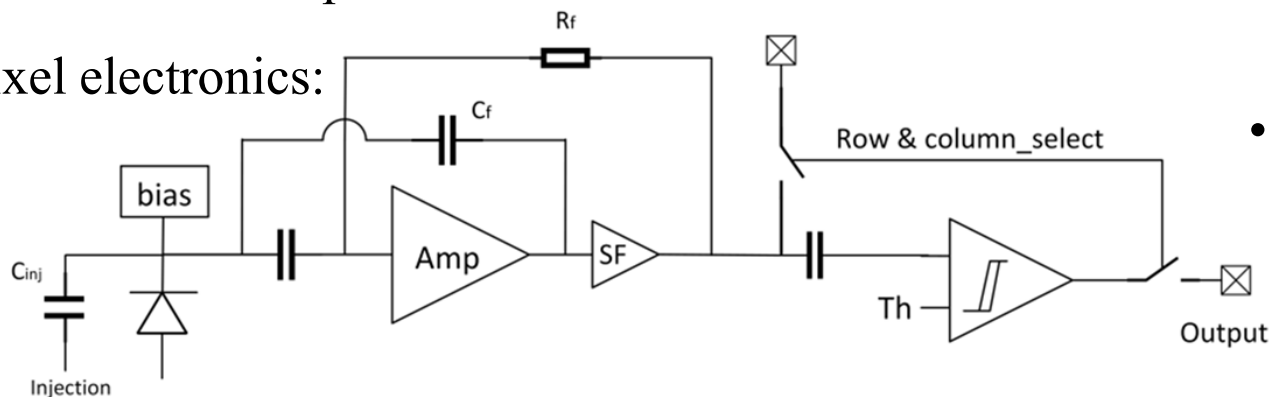


C-V curve

Section 1

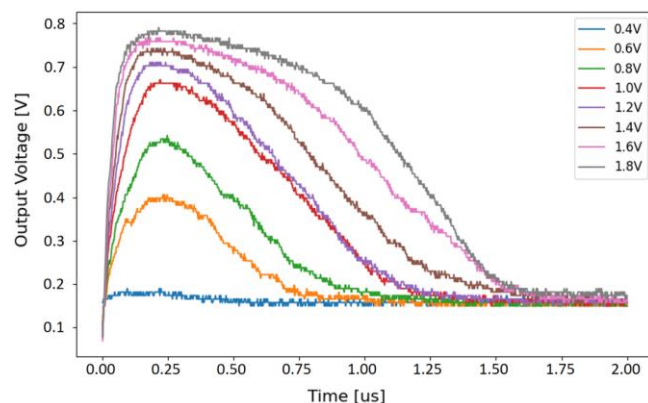
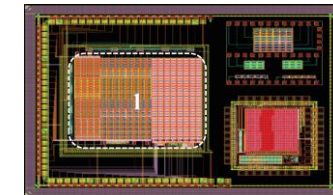
- Charge injection test: **JINST 20 (2025) C10011**
 - CSA waveform in expected
 - CSA response curve consistent with simulation

In-pixel electronics:

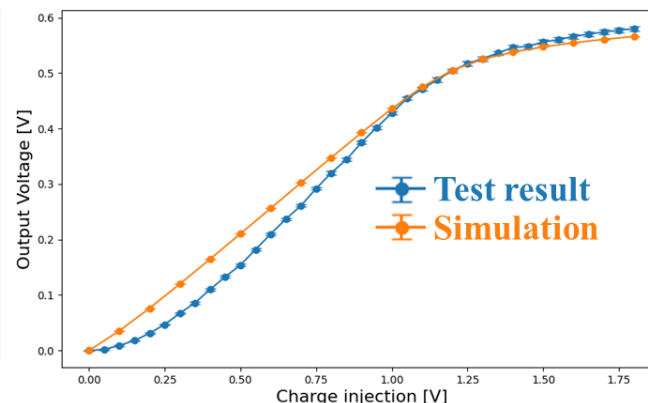


Radioactive sources test:

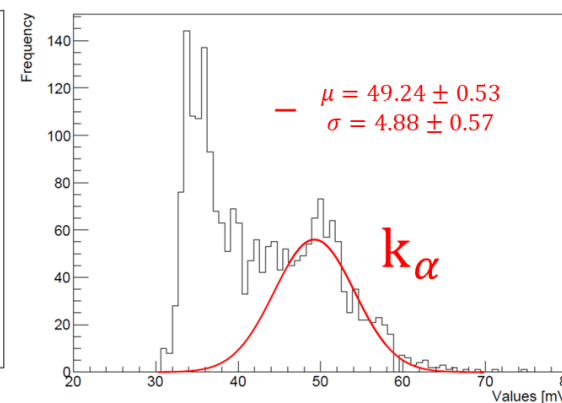
- ^{55}Fe (5.9 keV X-ray), Gaussian fit
 - $\mu \sim 49 \text{ mV} \sim 1640 \text{ e}^-$
 - $\sigma \sim 4.9 \text{ mV} \sim 160 \text{ e}^-$
- ^{90}Sr (β -source), Landau fit
 - MPV: $\sim 34 \text{ mV} \sim 1120 \text{ e}^-$
 - Depletion depth: $\sim 10 \mu\text{m}$



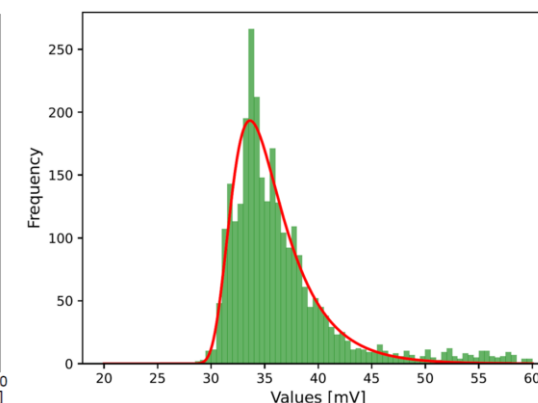
CSA output vs V_{inj}



CSA response curve



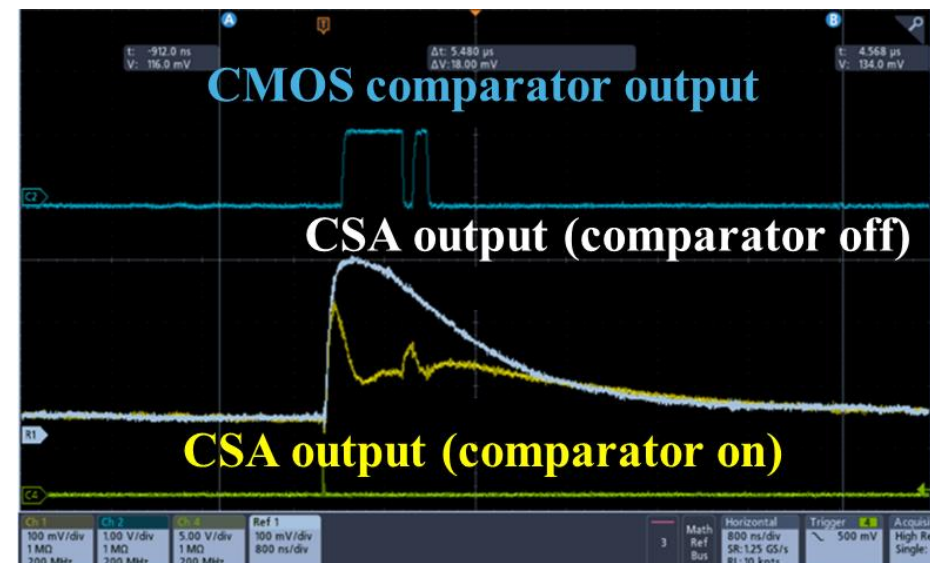
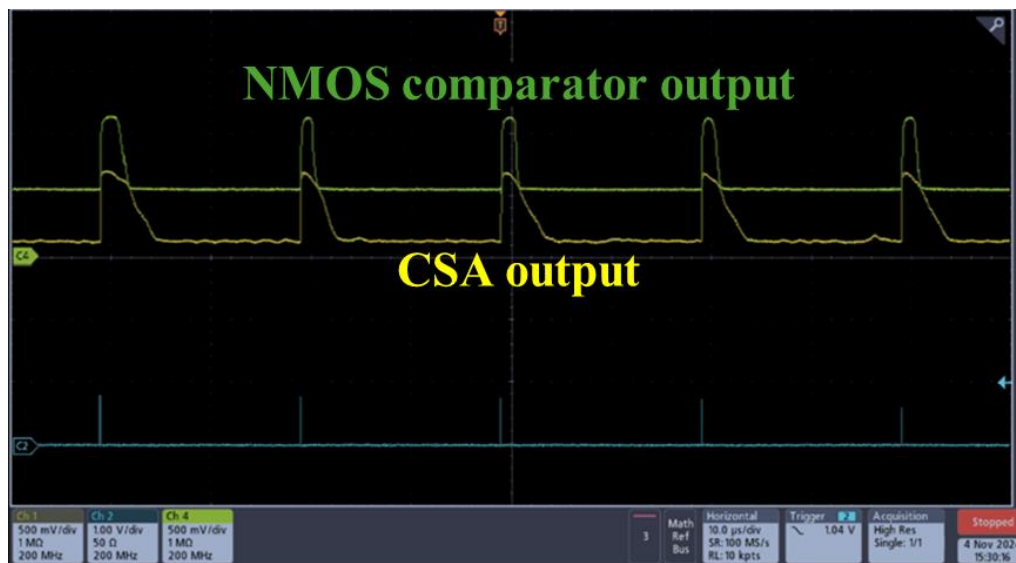
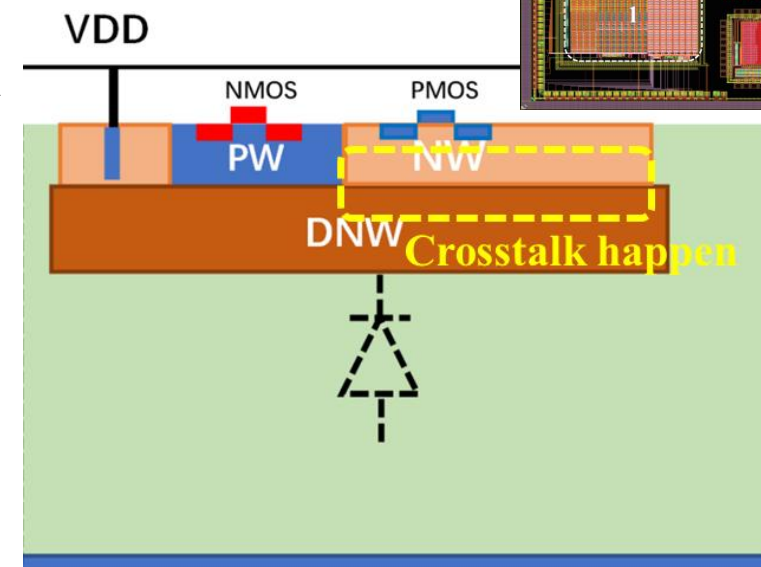
^{55}Fe test



^{90}Sr test

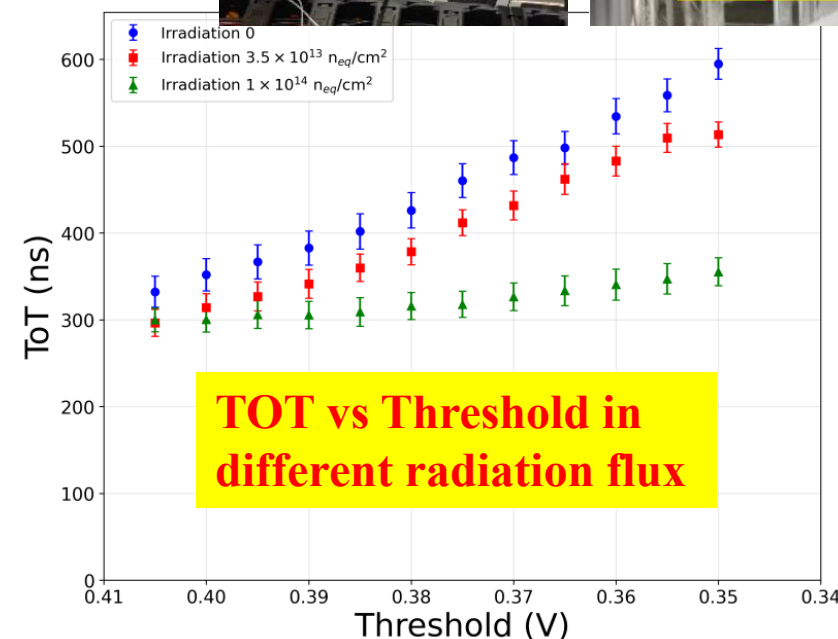
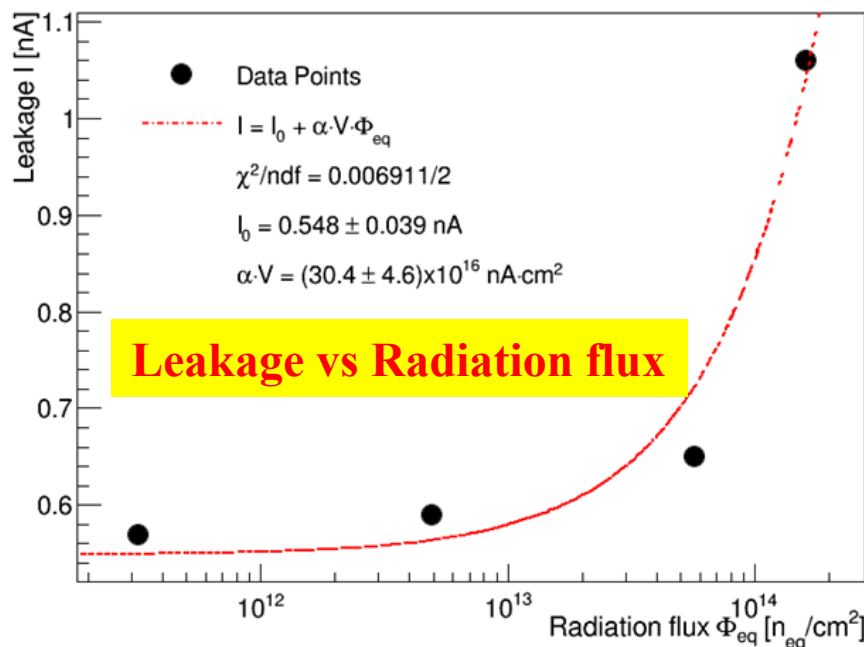
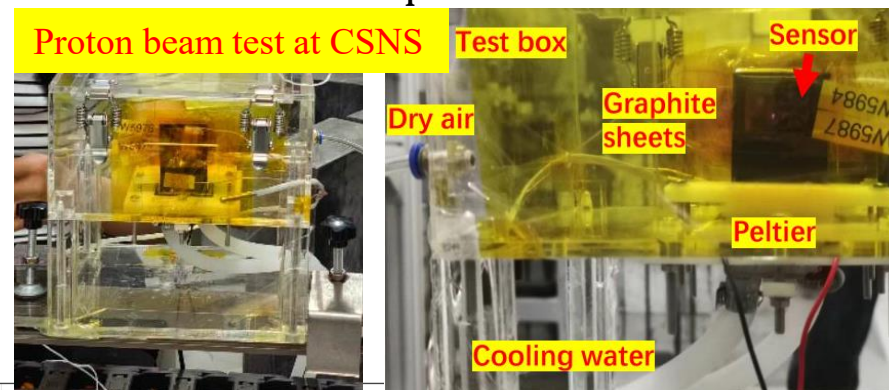
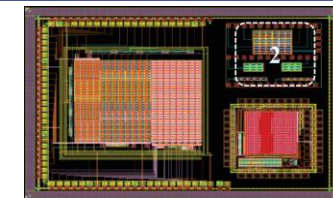
Section 1

- Laser test : **JINST 20 (2025) C10011**
 - Two different in-pixel comparator design: CMOS and NMOS-only
 - Pixel with NMOS-only designed work well
 - Crosstalk issue seen in CSA output waveform when CMOS comparator is on
 - Potential flip in digital circuitry cause the disturbance between N-well of PMOS bulk terminal and deep N-well
 - The crosstalk can be mitigated by adding a p-layer for isolation, process modification is required.



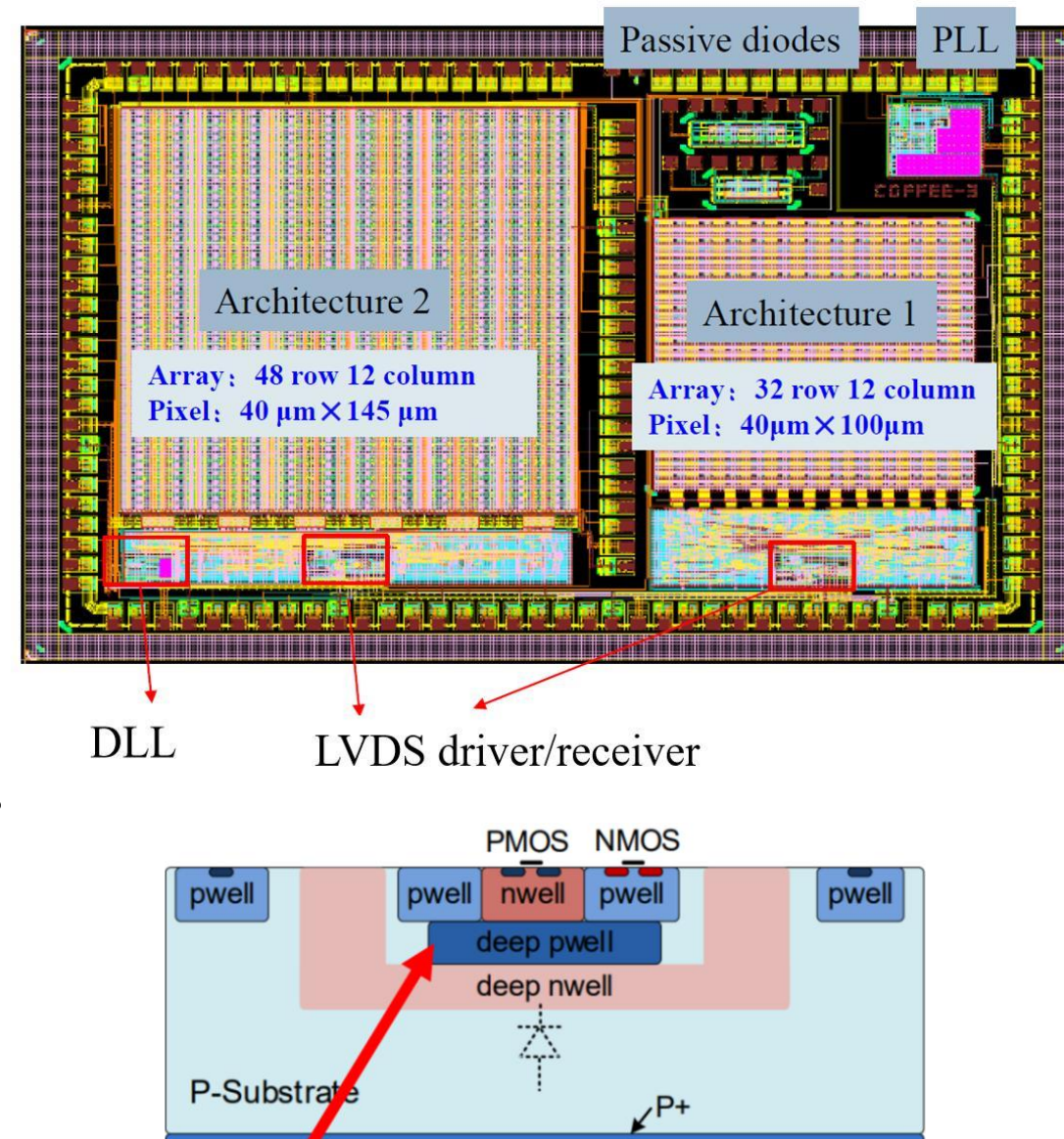
Radiation hardness test

- In LHCb UP Tracker, Radiation hardness target to $\sim 3 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
- Proton irradiation at CSNS (China Spallation Neutron Source), up to $1.3 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
- After $\sim 10^{14} \text{ n}_{\text{eq}}/\text{cm}^2$ radiation:
 - Leakage 10 pA $\rightarrow$ 1 nA
 - Capacitance and breakdown voltage remain unchanged
 - In-pixel circuit still work
- More studies are still ongoing



COFFEE3 chip, $3 \times 4 \text{ mm}^2$

- Passive diodes: same design as COFFEE2 chip, for further study of sensor and process
- Peripheral function modules: PLL, LVDS, DLL for IP accumulation and power consumption assessment
- Two pixel matrix readout architectures:
 - 1. CSA + NMOS design in-pixel, less crosstalk between analog and digital circuits
 - 2. CSA + CMOS design in-pixel, for future quadruple-well process. Advanced readout design, more suitable for high hit density situation
- Future quadruple-well process, add a deep p-well under n-well, reduce cross-talk between n-well and deep n-well



Pixels matrix array test system

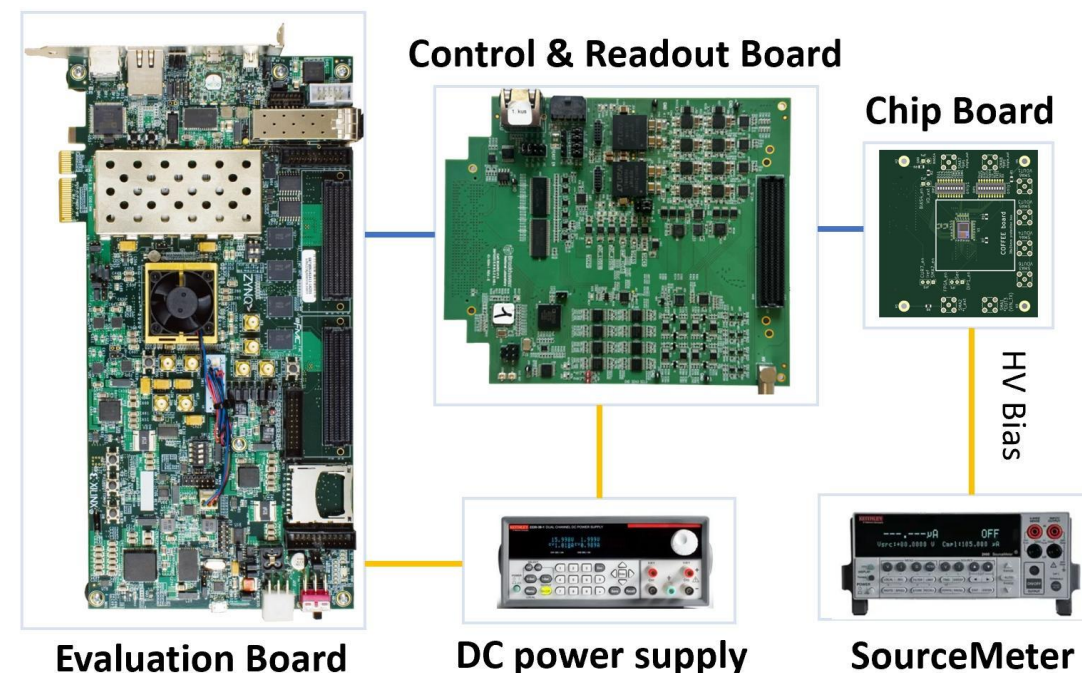
- Test platform based on Caribou system: power, clock, DAQ, slow-ctrl, fast-readout, ...
- PC + ZC706/ZCU102 + Caribou board + chip carrier board
- FE chip specific carrier board, firmware IP, software by ourself

Control and Readout (CaR) board

DRD3

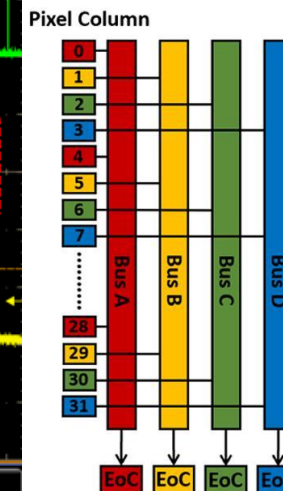
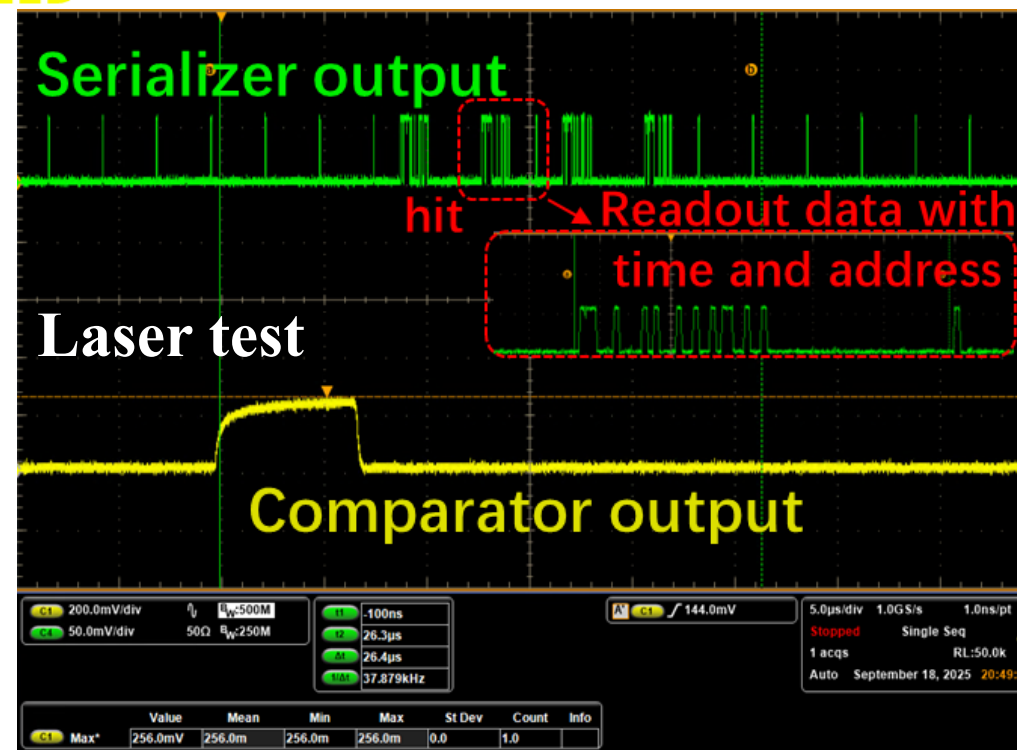
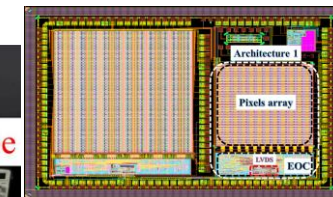
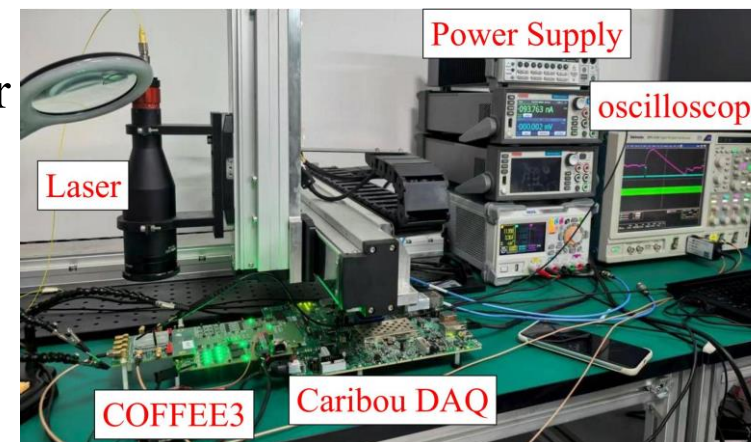
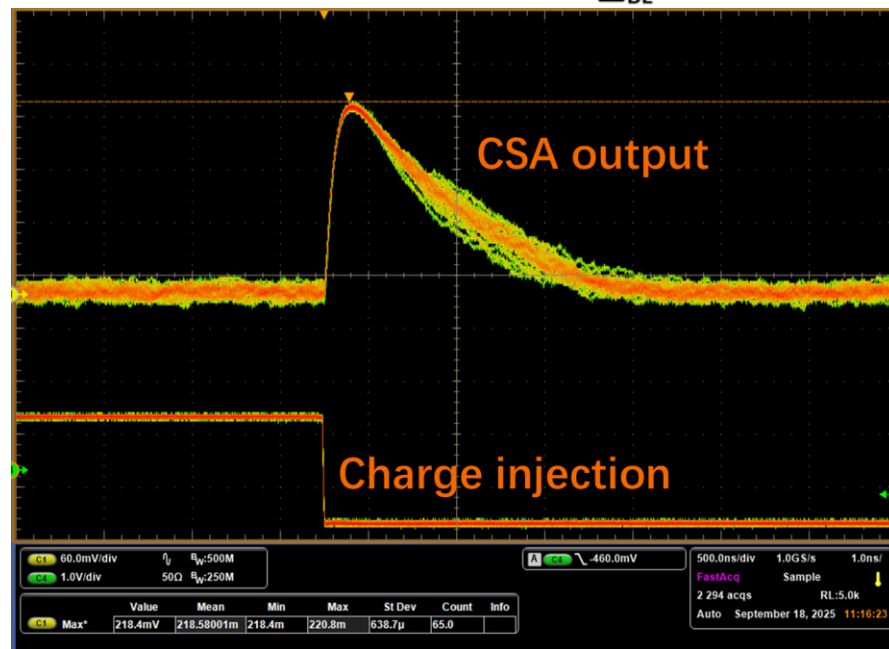
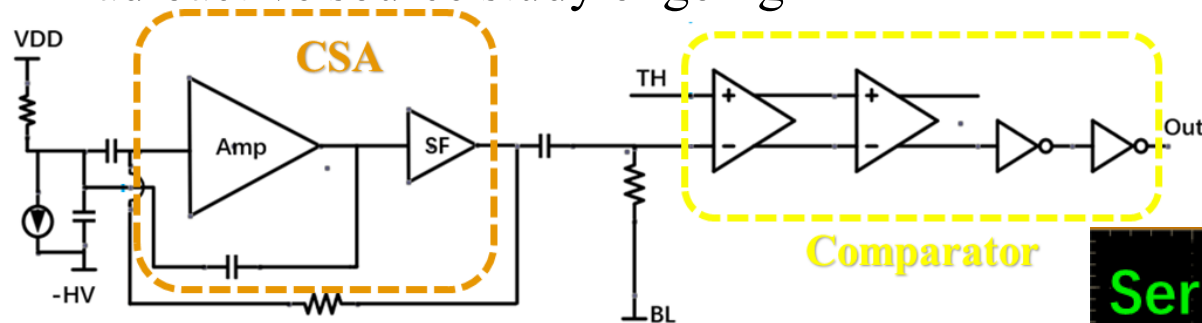
Feature	Description
Adjustable Power Supplies	8 units, 0.8 – 3.6 V, 3 A
Adjustable Voltage References	32 units, 0 – 4 V
Adjustable Current References	8 units, 0 – 1 mA
Voltage Inputs to Slow ADC	8 channels, 50 kSPS, 12-bit, 0 – 4 V
Analog Inputs to Fast ADC	16 channels, 65 MSPS, 14-bit, 0 – 1 V
Programmable Injection Pulsers	4 units
Full-Duplex High-Speed GTx Links	8 links, <12 Gbps
LVDS Links	17 bidirectional links
Input/Output Links	10 output links, 14 input links, 0.8 – 3.6 V
Programmable Clock Generator	Included
External TLU Clock Reference	Included
External High-Voltage (HV) Input	Included
FEAST Module Compatibility	Supported
FMC Interface to FPGA	Included
SEARAY Interface to Detector Chip	320-pin connector

Resources for various target applications



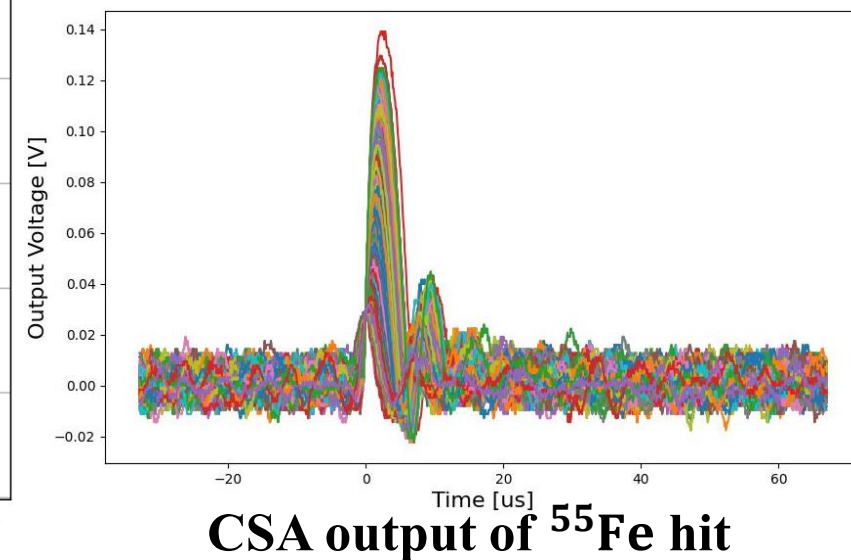
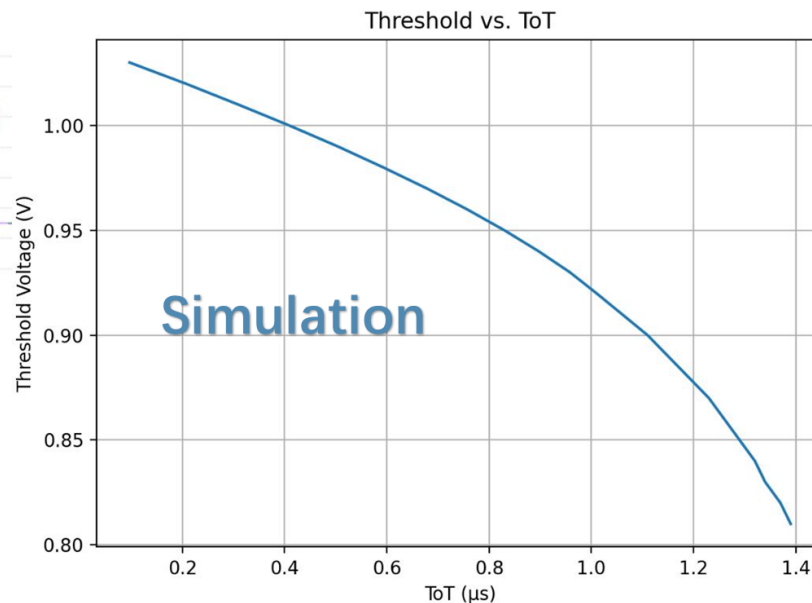
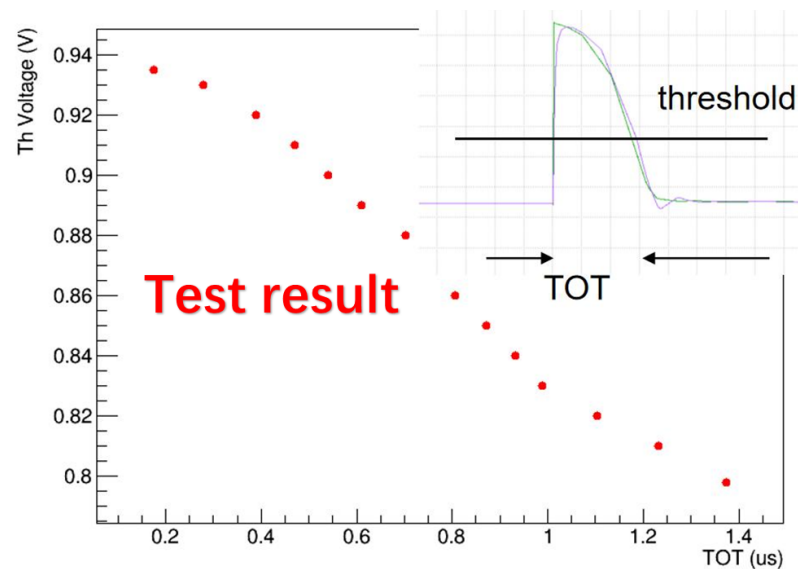
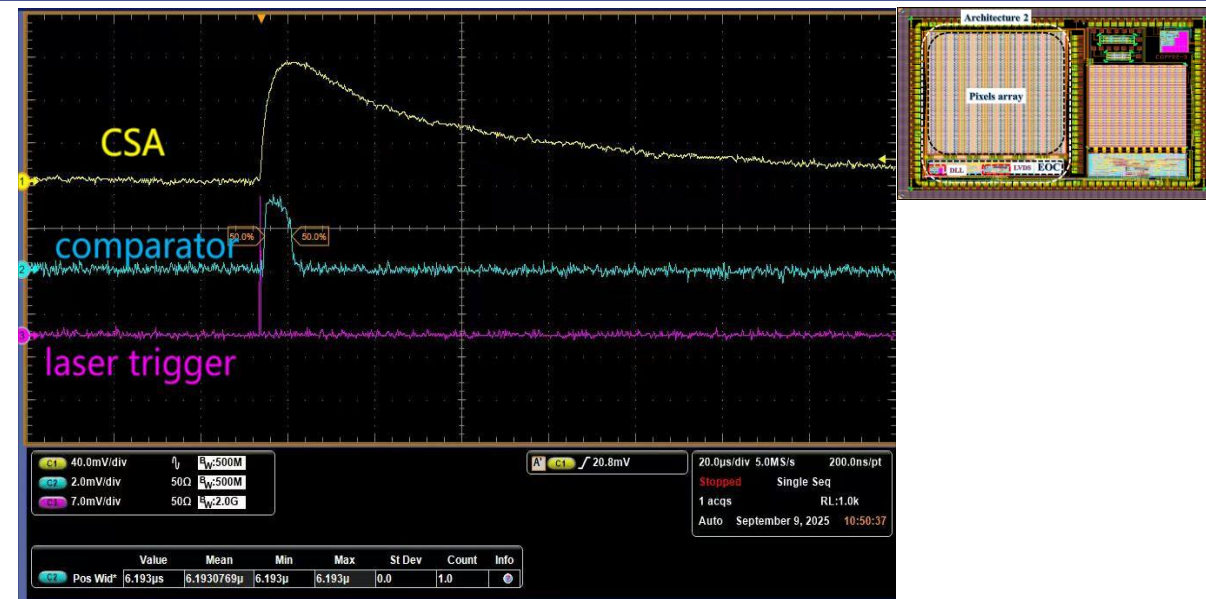
Architecture 1 test

- In-pixel circuit working well with charge injection and laser
- Digital readout function validated
- Radioactive source study ongoing



Architecture 2 test

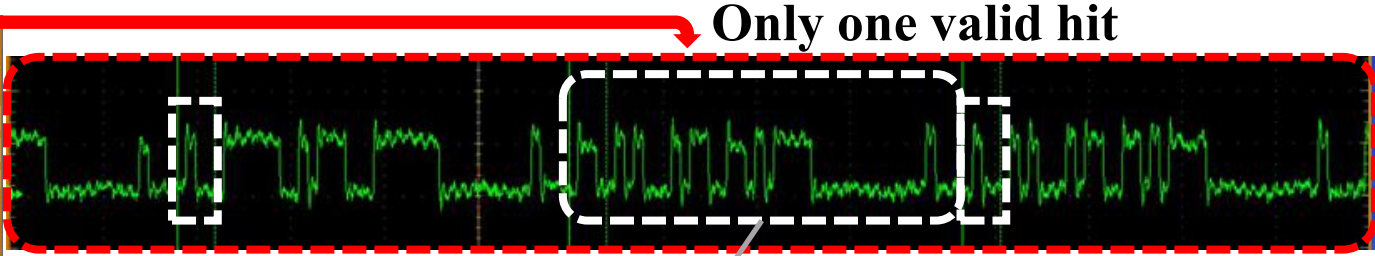
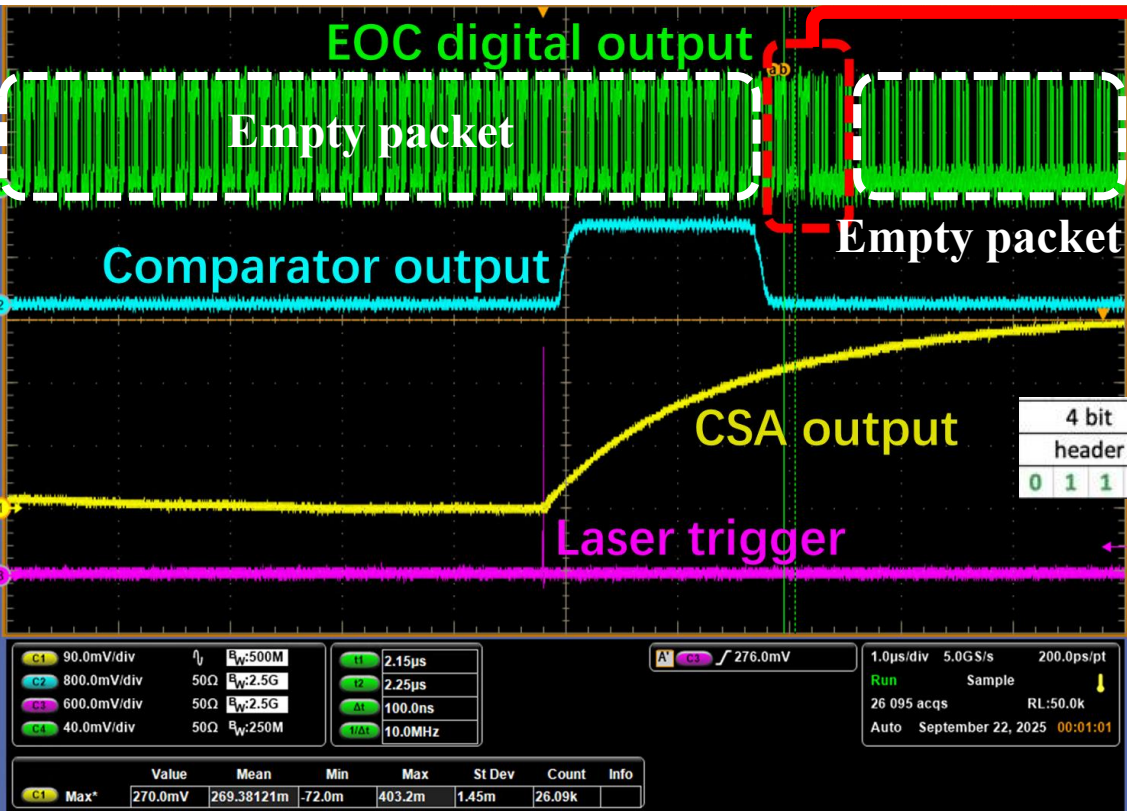
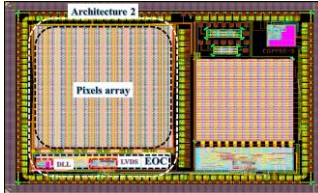
- In-pixel CSA and comparator output for laser signal
 - Typical time over threshold (TOT) of laser signal is consistent with simulation
- CSA response of ^{55}Fe signal can be seen, more study in near future



Architecture 2 test

- Full readout chain works well with laser test
 - Only unmask pixel column 0, row 1

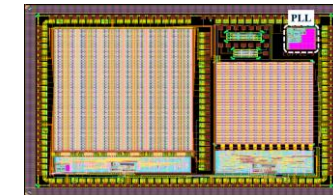
Sensor diode → in-pixel (CSA, comparator, TDC) → End of column readout circuit → DAQ



4 bit header	4 bit CHIP_TS	8 bit LE_coarse	8 bit TE_coarse	6 bit LE_fine	2 bit TE_fine	7 bit Addr_Row	3 bit Addr_Col
0 1 1 0	0 1 0 1	0 0 0 1 0 1 1 0	0 0 1 1 0 1 0 1 1	1 1 0 0 0 0	0 0	0 0 0 0 0 0 1	0 0 0

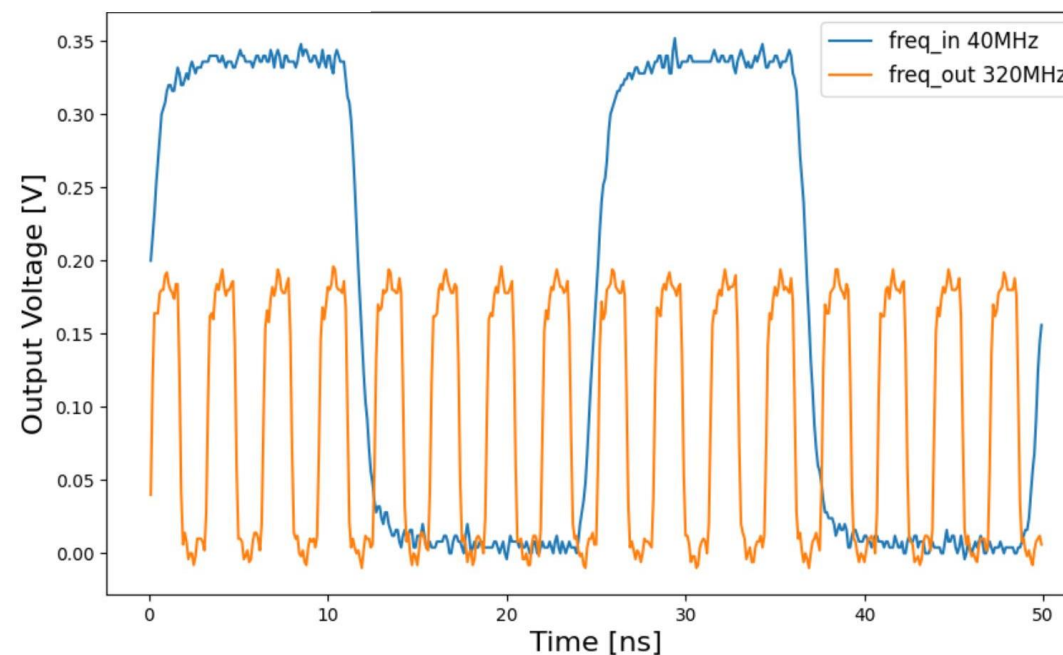
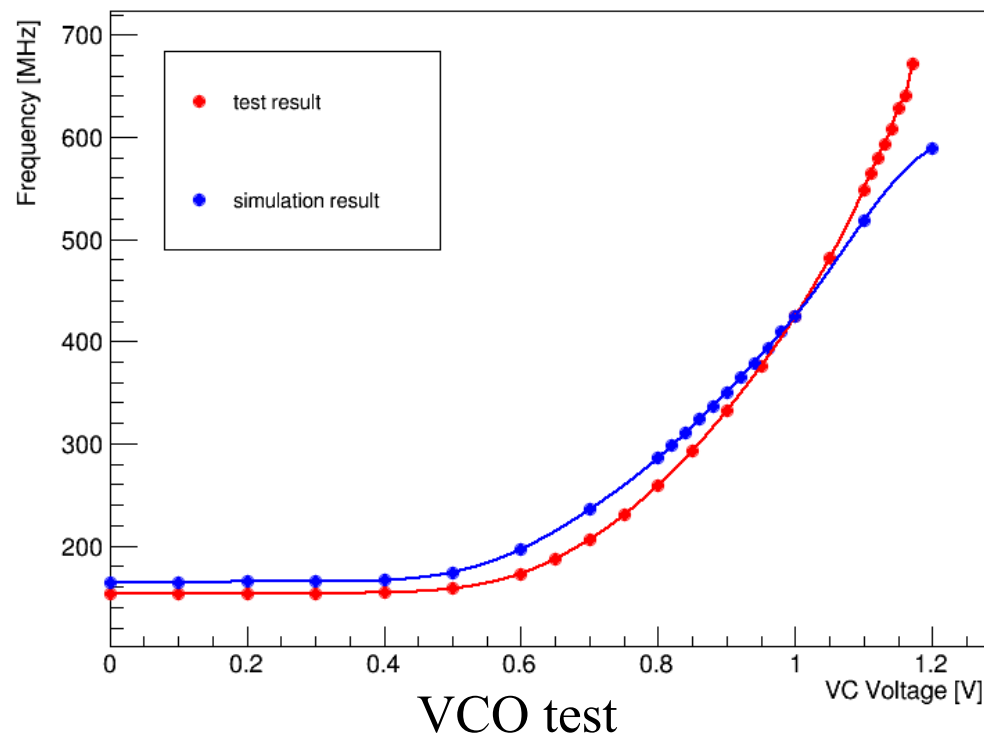
Valid hit
header: 0110

Row and column
address are correct



Phase locked loop (PLL) module

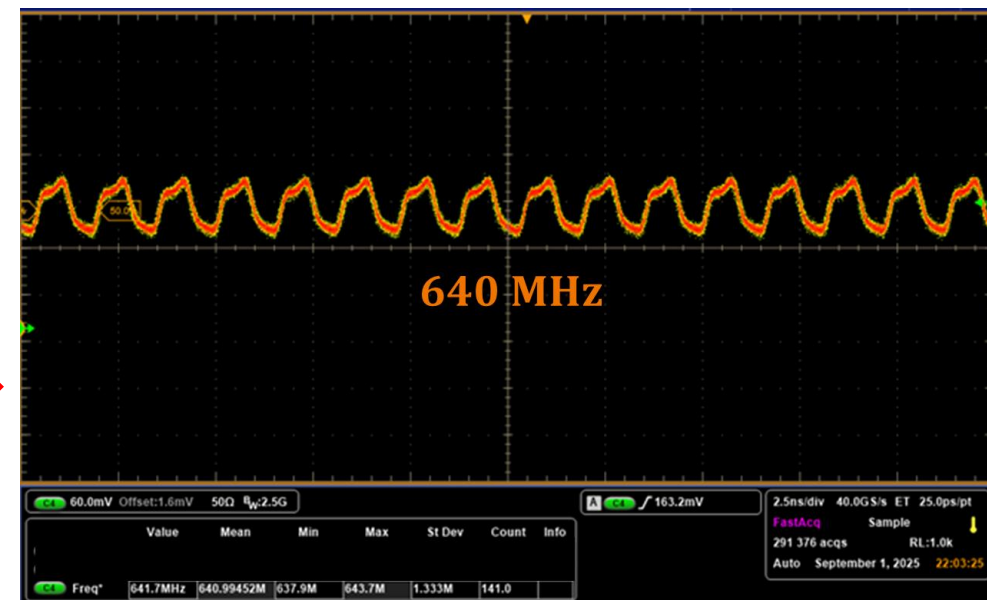
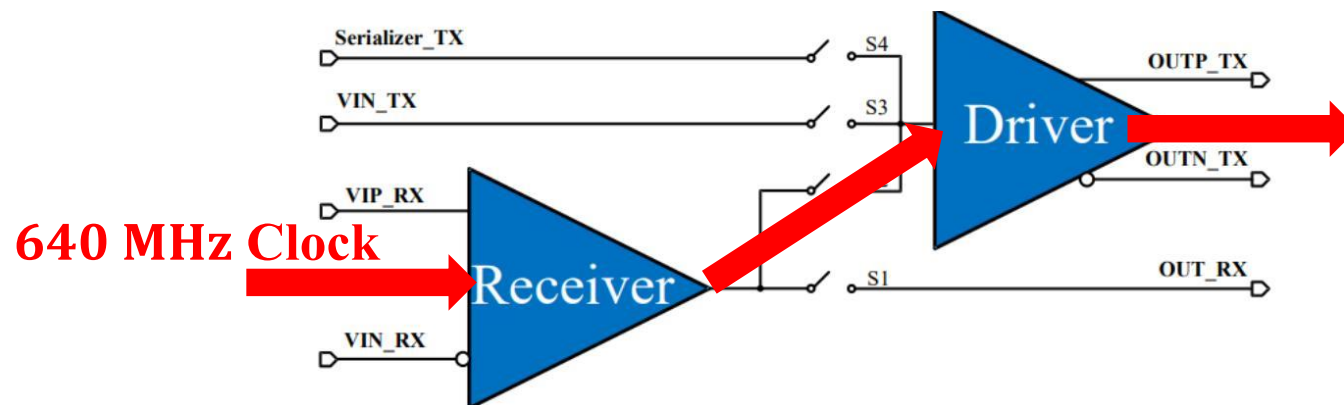
- Design for synchronizing the clock among chips and back-end DAQ
- Input CLK to generate internal clock to support TDC, high speed data transmission
- Voltage-Controlled Oscillator (VCO) and frequency multiply functions (x4, 8, 16) work well within the range up to 640 MHz
- Working fine from the room temperature to $-50\text{ }^{\circ}\text{C}$



8x test, input 40 MHz, output 320 MHz

Peripheral circuit

- Data **LVDS** transceiver works up to 640 MHz supporting to 1.28 Gbps data transmission, to reduce common mode noise

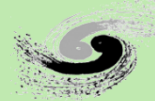


- Delay Locked Loop (**DLL**) delivers clock phase delay as expected, to eliminate timing errors generated during the transmission of clock signals within the chip
- Following successful validation, these modules (PLL, LVDS, DLL) can be used in future large chips



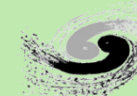
- HVCMOS prototyping chip in 55 nm process for UP at LHCb Upgrade II
- Many encouraging results from COFFEE chip:
 - Breakdown Voltage > 70 V, leakage ~ 10 pA
 - Two full readout pixel matrixes work well
- Future plan:
 - Full characterization of COFFEE3 chip:
 - Spatial and timing resolution, power consumption, radiation hardness
 - Seek process optimization for future chip design

Thanks for your attention!



Back up

COFFEE1 Brief Result

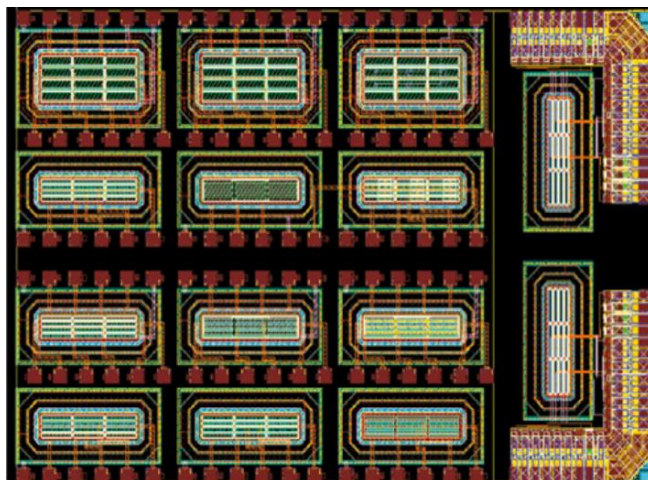


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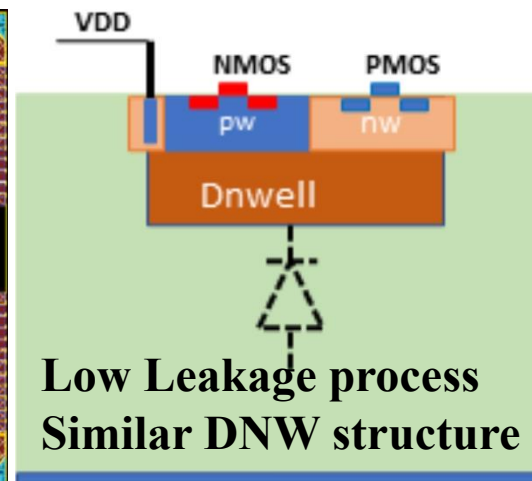


COFFEE1 chip, $3 \times 2 \text{ mm}^2$, verify the feasibility of 55 nm process. NIMA 1069 (2024) 169905

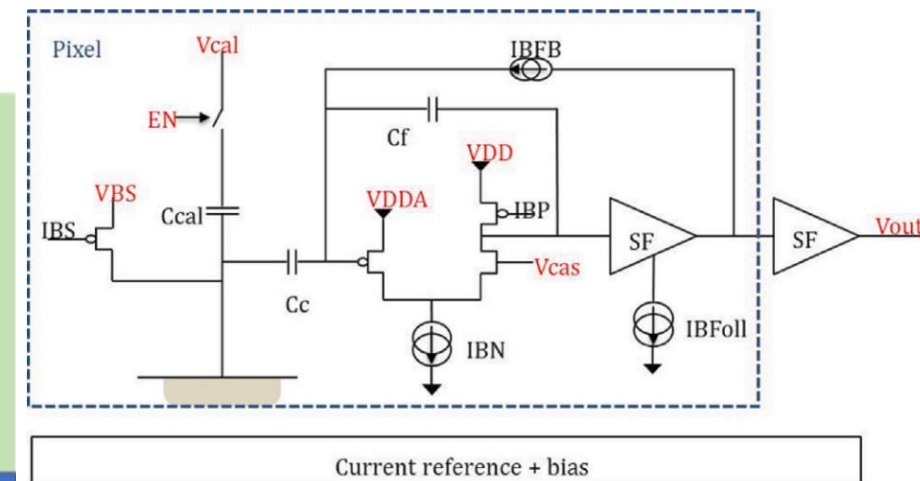
Pixel area
P-stop
DNW gap



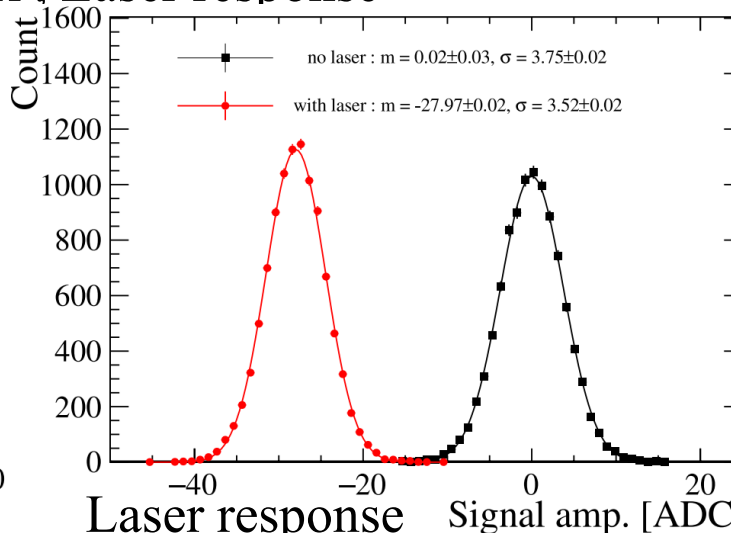
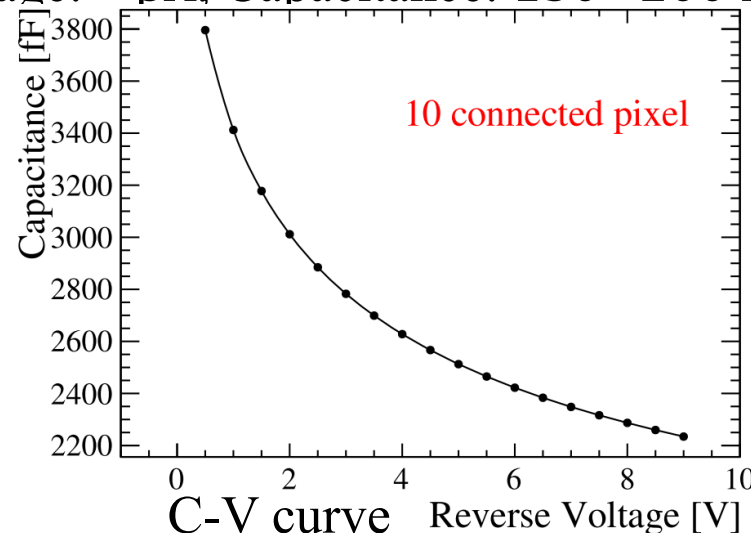
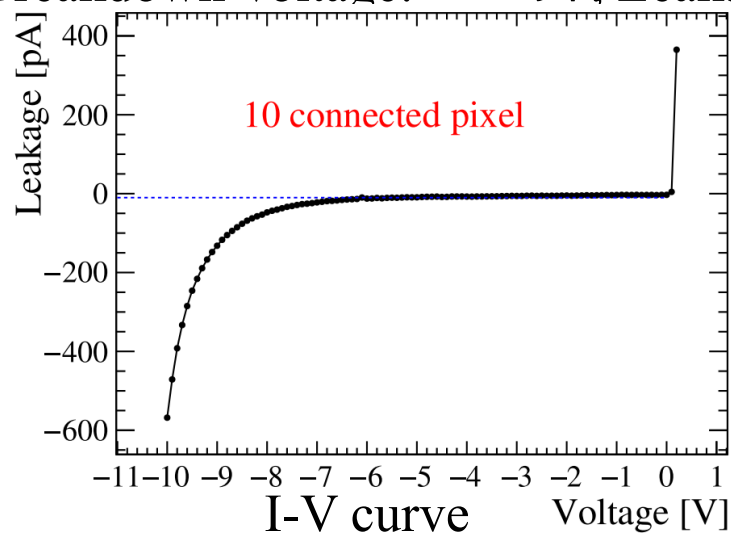
COFFEE1 chip floorplan



Sensor cross section Schematic design of COFFEE1 in-pixel circuit



Breakdown Voltage: $\sim -9\text{V}$, Leakage: $\sim \text{pA}$, Capacitance: $150\sim 200 \text{ fF}$, Laser response



Section 3

- Charge injection test: **JINST 20 (2025) C03023**
 - CSA waveform in expected
- Radioactive sources test:
 - ^{55}Fe (5.9 keV X-ray), Gaussian fit
 - $\mu \sim 73 \text{ mV} \sim 1640 \text{ e}^-$
 - $\sigma \sim 2.6 \text{ mV} \sim 58 \text{ e}^-$
 - ^{90}Sr (β -source), Landau fit
 - MPV: $\sim 50 \text{ mV} \sim 1100 \text{ e}^-$
 - Depletion depth: $\sim 10 \mu\text{m}$

Test setup:

